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Jang et al.

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(54) **GAS DISPERSING PLATE FOR SEMICONDUCTOR MANUFACTURING APPARATUS**

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(**) Term: **15 Years**

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(52) **U.S. Cl.**
USPC **D23/259**

(58) **Field of Classification Search**
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414/217, 935-941; D12/197; D13/182;
D15/144, 144.1; 118/715
CPC C23C 16/505; C23C 16/4407; C23C
16/4404; C23C 16/45565
See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a gas dispersing plate for a semiconductor manufacturing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a perspective view of a gas dispersing plate for a semiconductor manufacturing apparatus.
FIG. 2 is a front elevational view of the gas dispersing plate.
FIG. 3 is a rear elevational view of the gas dispersing plate.
FIG. 4 is a left side elevational view of the gas dispersing plate.
FIG. 5 is a right side elevational view of the gas dispersing plate.
FIG. 6 is a top plan view of the gas dispersing plate.
FIG. 7 is a bottom plan view of the gas dispersing plate.
FIG. 8 is a cross-sectional view taken along line 8-8 of FIG. 6; and,
FIG. 9 is an enlarged detail view of FIG. 7.

1 Claim, 6 Drawing Sheets

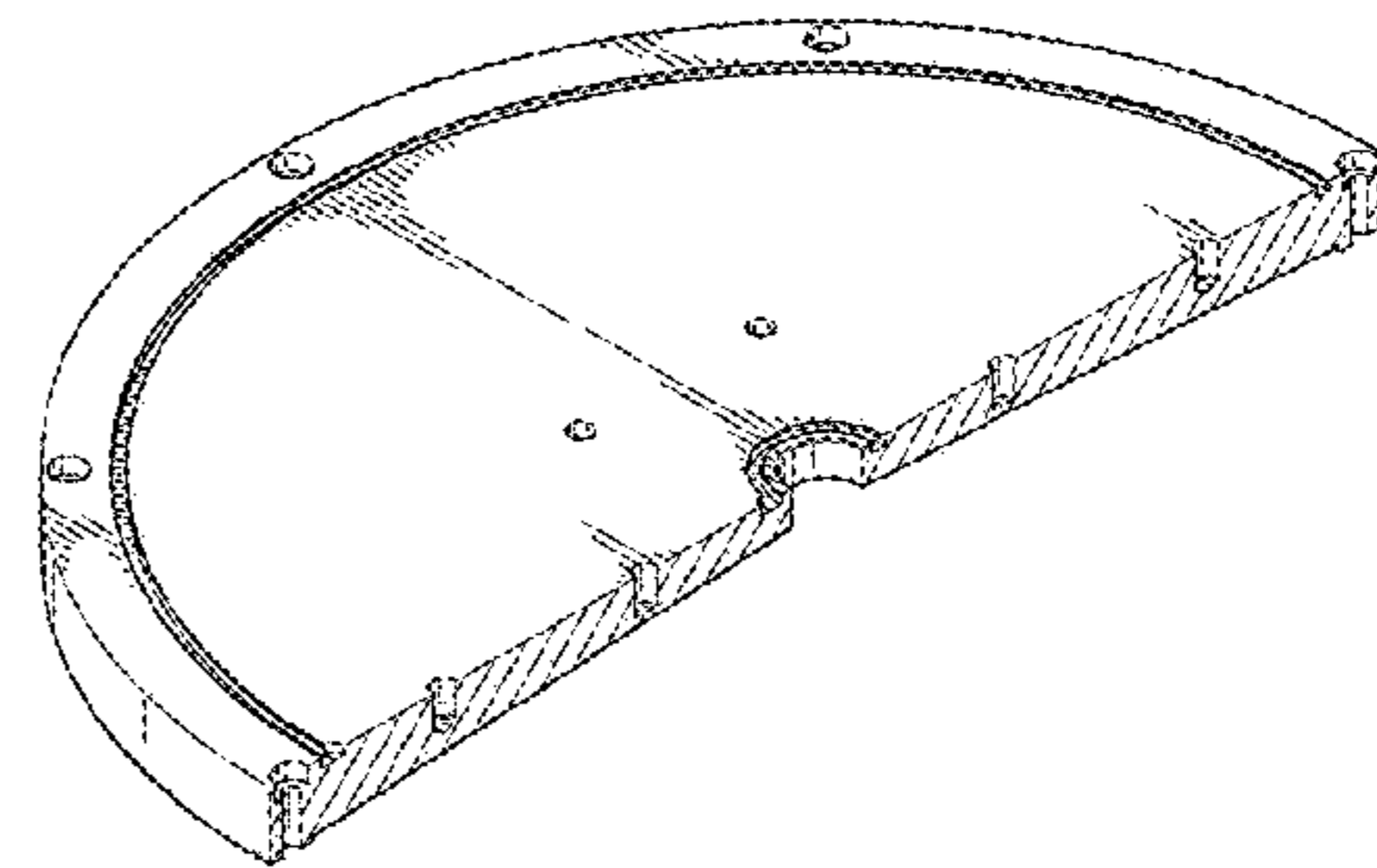
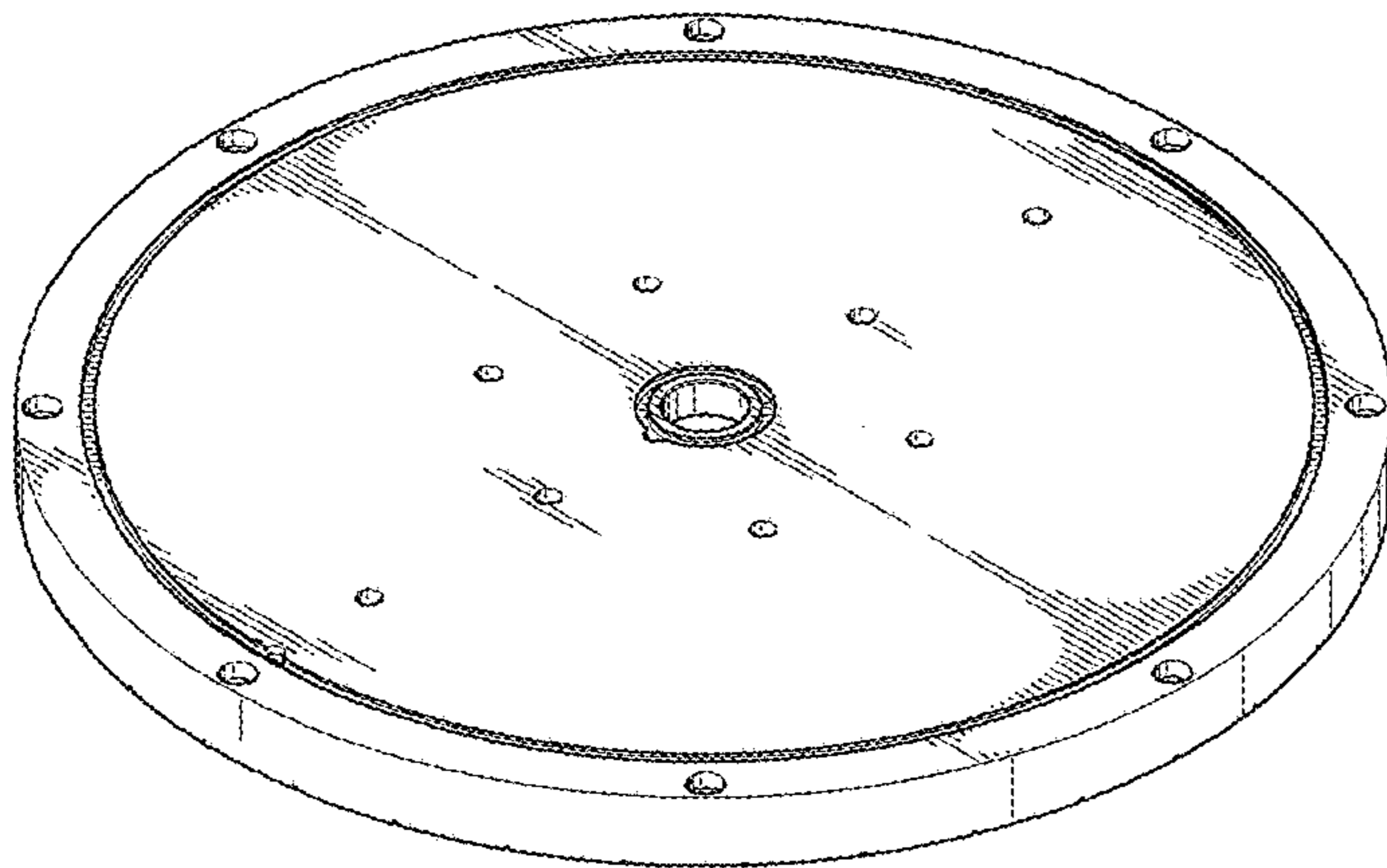


FIG. 1

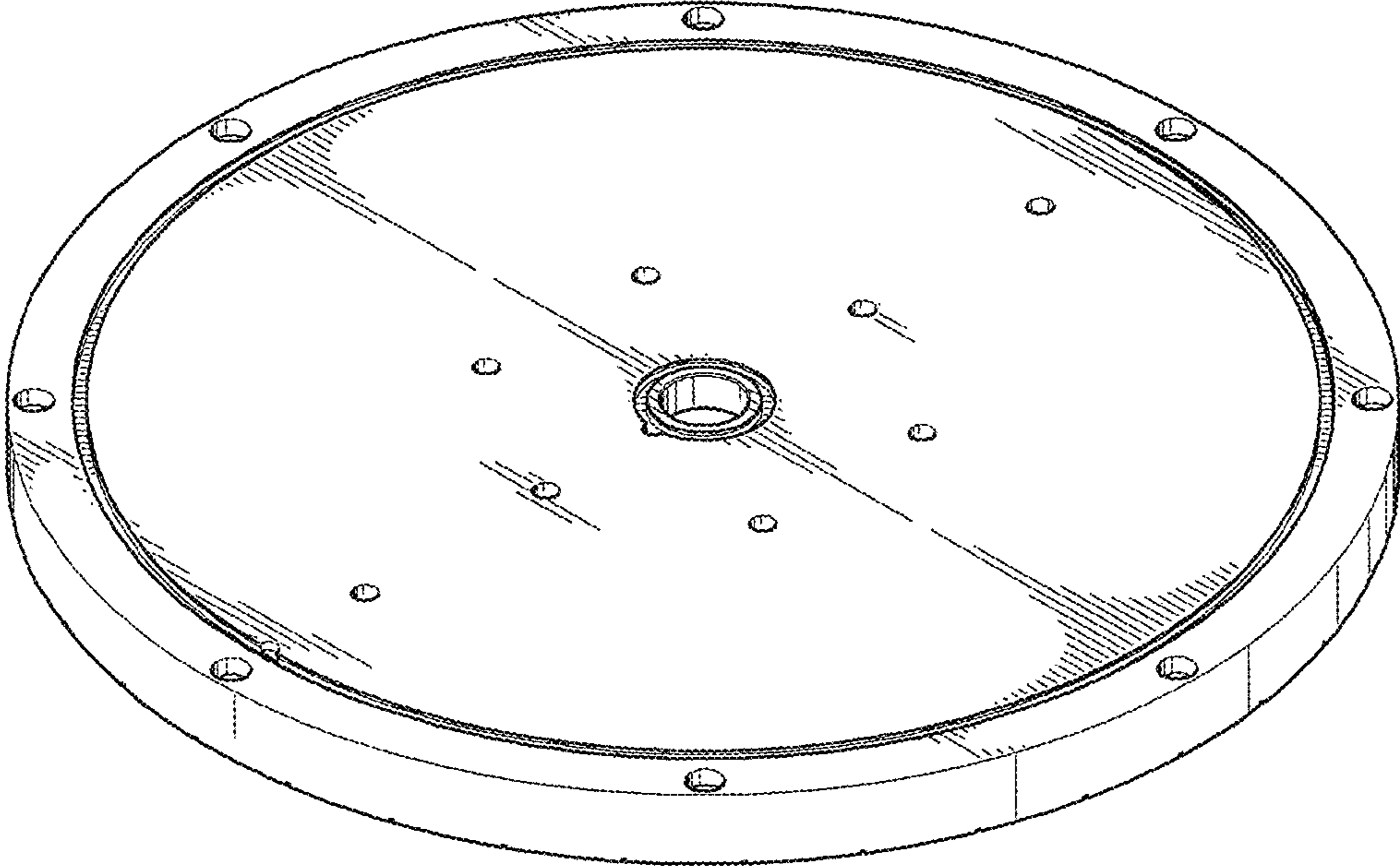


FIG. 2



FIG. 3



FIG. 4



FIG. 5



FIG. 6

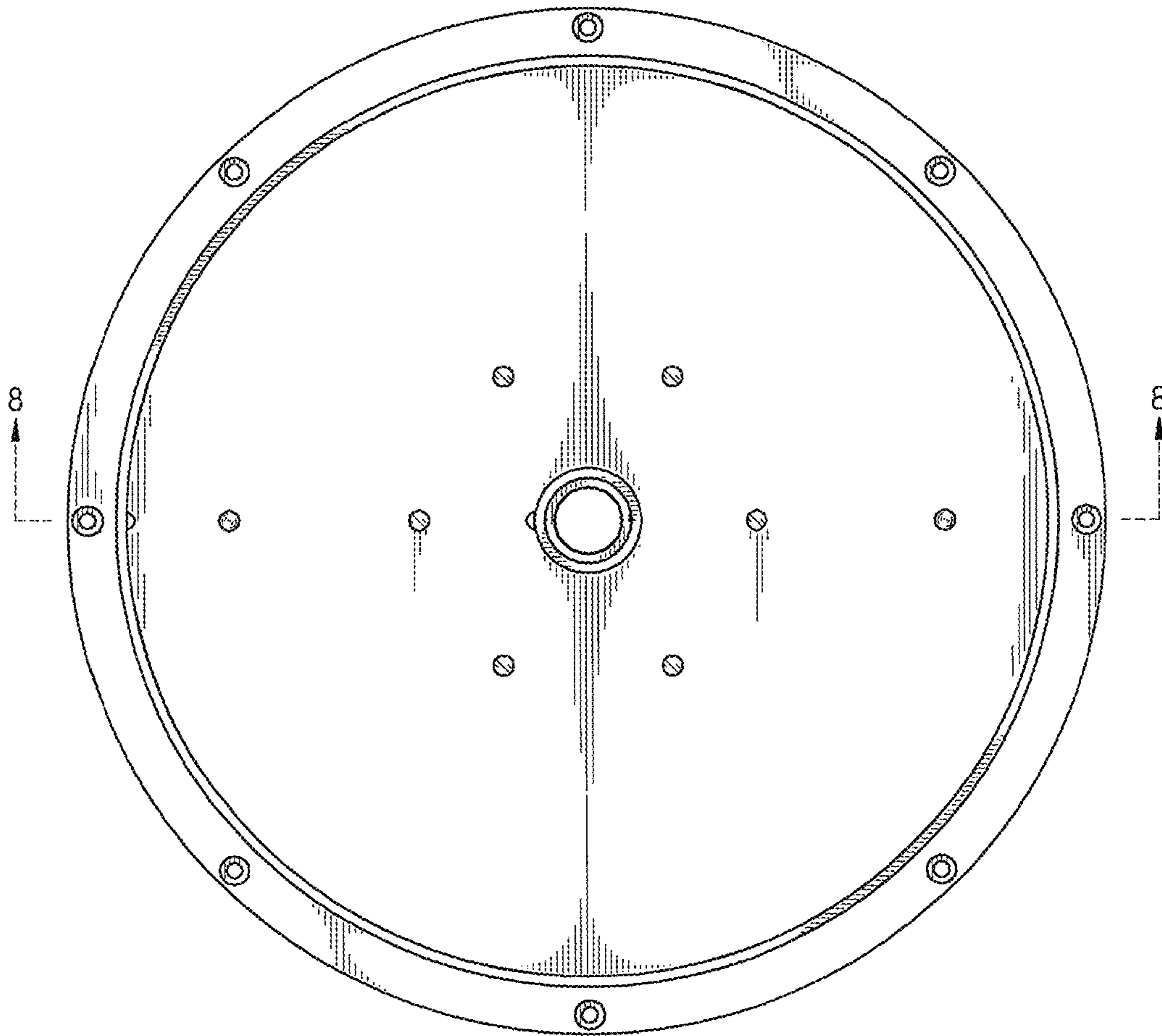


FIG. 7

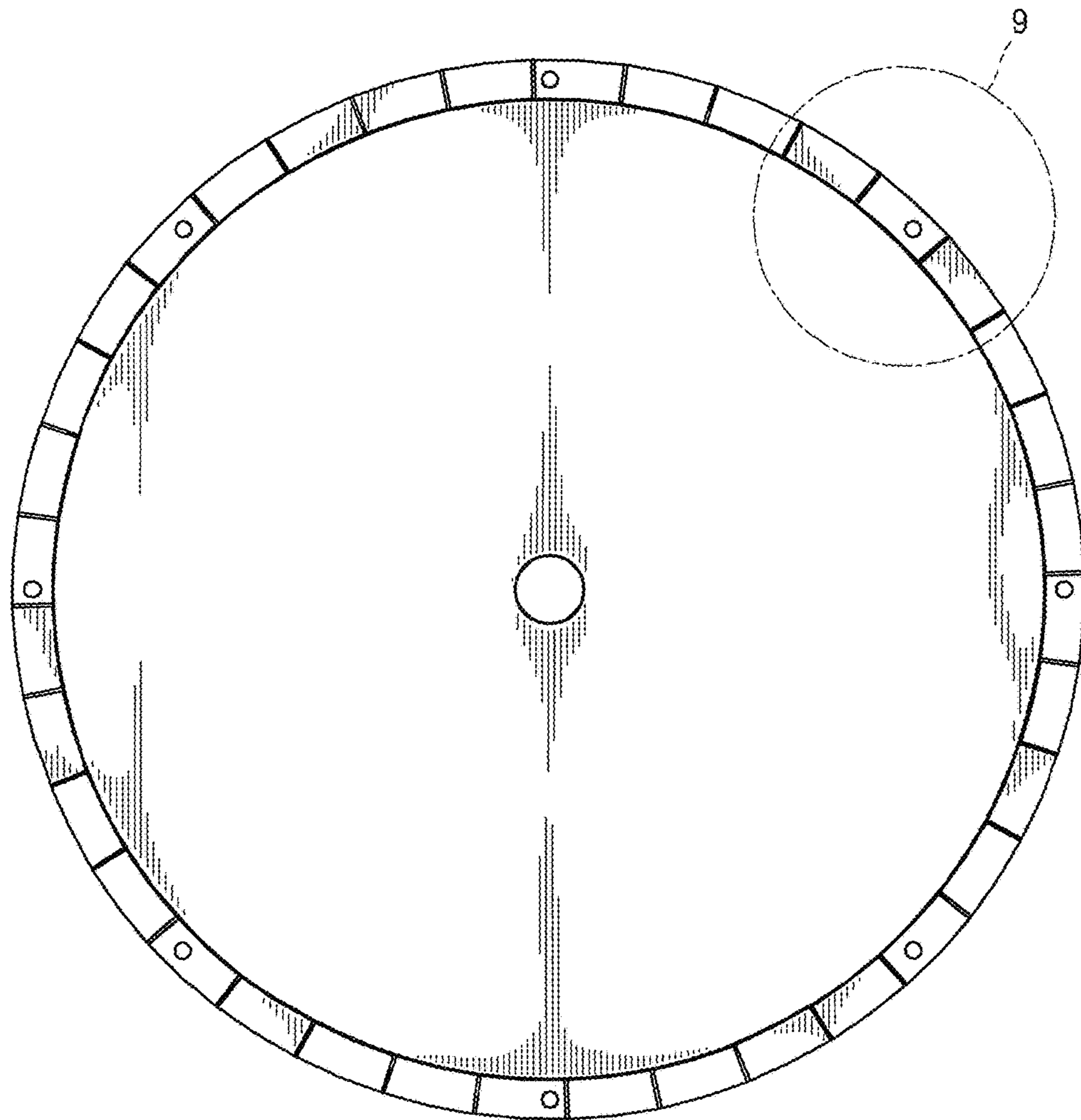


FIG. 8

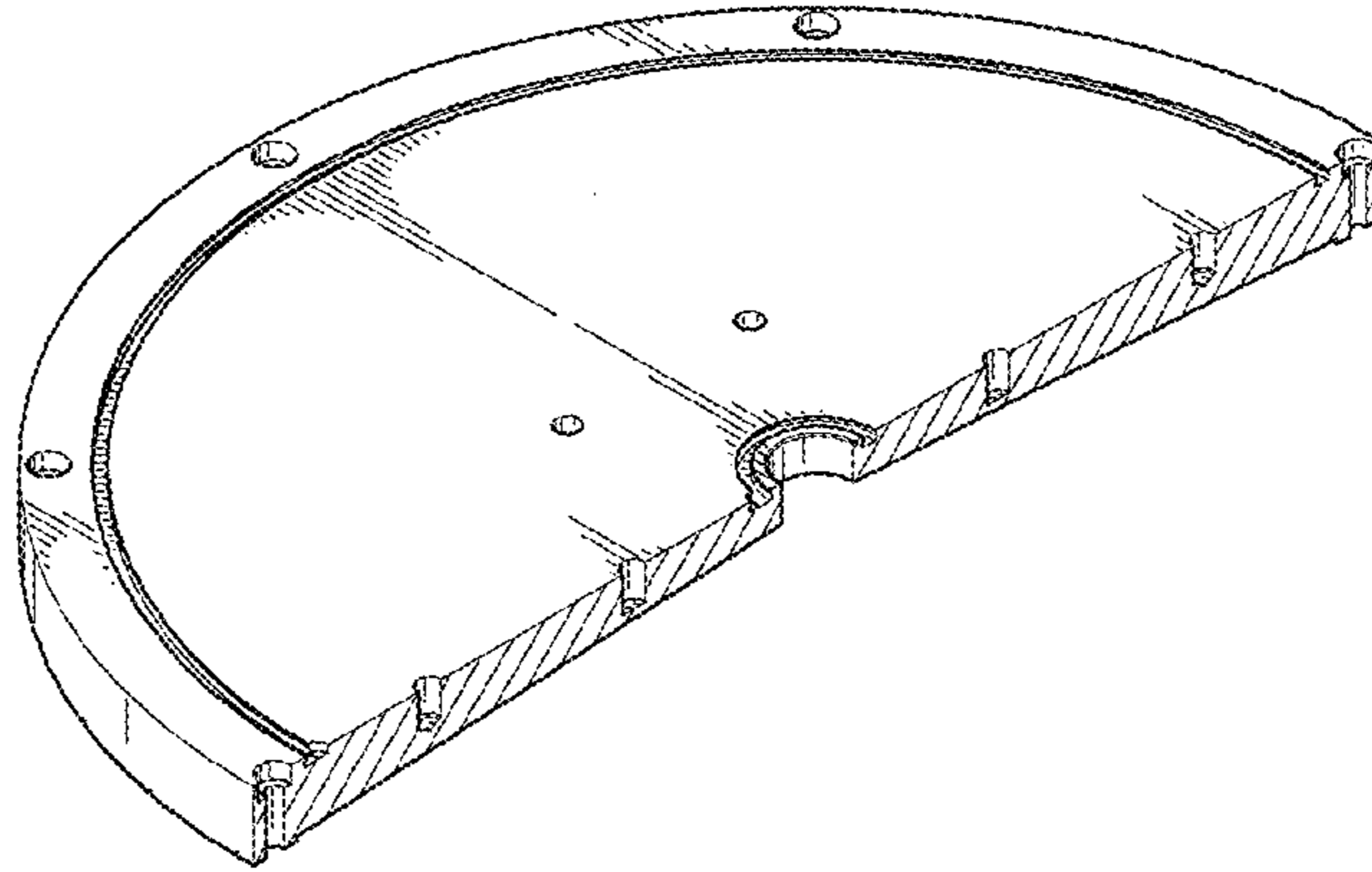


FIG. 9

